

A Method for Resuming a Wire Sawing Process of a Workpiece after an Unplanned Interruption

The present invention relates to a method for resuming an interrupted process for sawing a workpiece into a multiplicity of wafers with a wire saw. The method according to the invention will be explained here with reference to the example of a process for sawing a workpiece of semiconductor material into a multiplicity of wafers with a wire saw, although it is also suitable for workpieces of other materials.

For electronics, microelectronics and micro-electromechanics, semiconductor wafers with extreme requirements for global and local planarity, one-side referenced local planarity (nanotopology), roughness and cleanness are needed as starting materials (substrates). Semiconductor wafers are wafers of semiconductor materials, in particular compound semiconductors such as gallium arsenide and predominantly elementary semiconductors such as silicon and sometimes germanium.

According to the prior art, semiconductor wafers are produced in a multiplicity of successive process steps: in a first step, for example, a single crystal (rod) of semiconductor material is pulled by the Czochralski method or a polycrystalline block of semiconductor material is cast, and in a further step the resulting circular-cylindrical or block-shaped workpiece of semiconductor material (ingot) is cut into individual semiconductor wafers by wire sawing.

Wire saws are used in order to cut a multiplicity of wafers from a workpiece made of semiconductor material. DE 195 17 107 C2 and US-5,771,876 describe the functional principle of a wire saw which is suitable for the production of semiconductor wafers. The essential components of these wire saws include a machine frame, a forward feed device and a sawing tool, which

consists of a web (wire web) of parallel wire sections. The spacing of the wires in the wire web depends on the desired target thickness of the wafers to be cut, and for semiconductor material wafers is for example from 100 to 1000 μm .

DE 101 47 634 B4 describes a method for cutting wafers of semiconductor material from a single crystal, the single crystal being rotated about a longitudinal axis during the cutting of the semiconductor wafers while penetrating into the sawing wires of two wire webs of a wire saw, the sawn wafers of semiconductor material having parallel rotationally symmetrical curved sides.

In general, the wire web is formed by a multiplicity of parallel wire sections which are tensioned between at least two wire guide rollers, the wire guide rollers being rotatably mounted and at least one of them being a driven roll.

The wire sections may belong to a single finite wire, which is guided spirally around the system of rollers and is unwound from a stock spool onto a receiver spool. Patent specification US 4,655,191, on the other hand, discloses a wire saw in which a multiplicity of finite wires are provided and each wire section of the wire web is assigned to one of these wires. EP 522 542 A1 also discloses a wire saw in which a multiplicity of endless wire loops run around the system of wire-guide rollers.

During the cutting process, the workpiece passes through the wire web, in which the sawing wire is arranged in the form of wire sections lying parallel to one another. The passage through the wire web is brought about by means of a forward feed device, which moves the workpiece against the wire web, the wire web against the workpiece or the workpiece and the wire web against one another.

When the wire web penetrates into the workpiece, according to the prior art, for a defined time and with a particular speed, a defined length of the sawing wire is fed forward (wire forward) and a further defined length is fed back (wire backward), the backward length WBL generally being shorter than the forward length (WFL). This sawing method is also referred to as a reciprocating movement method and is disclosed, for example, in DE 39 40 691 A1 and in US 2010 1630 10 A2.

EP 1 717 001 B1 teaches that a forward movement and a backward movement are carried out when sawing a workpiece with a wire saw, the length of the wire during the backward movement (WBL) being shorter than the length of the wire during the forward movement (WFL).

DE 11 2008 003 321 T5 discloses, for removal of the wire web from a sawn workpiece, a wire running length in the forward and backward directions respectively of 1 m or less and a wire running speed of 2 m/min or less.

The sawing of a workpiece into many wafers with a wire saw is carried out in the presence of a liquid cutting medium, which inter alia is used to transport the material abraded by the sawing wire out of the sawing kerf, and according to the prior art is applied onto the sawing wire.

If the sawing wire is covered with an abrasive coating, for example diamond, a cutting medium without free abrasive is generally used. When using wire saws comprising a sawing wire without fixedly bonded abrasive, the abrasive is supplied in the form of a suspension (cutting medium suspension, sawing slurry, slurry) during the cutting process.

When cutting wafers from a workpiece made of semiconductor material, it is conventional for the workpiece to be connected

to a sawing strip into which the sawing wire cuts at the end of the process. The sawing strip is for example a graphite strip, which is adhesively bonded or cemented on the lateral face of the workpiece. The workpiece with the sawing strip is then cemented on a support body. After the cutting, the resulting semiconductor wafers remain fixed on the sawing strip like the teeth of a comb, and can thus be removed from the wire saw. Subsequently, the remaining sawing strip is separated from the semiconductor wafers.

The production of semiconductor wafers from workpieces made of semiconductor material, for example from a circular-cylindrical rod of a single crystal or a cuboid polycrystalline block, places great demands on the wire sawing. The aim of the sawing process is generally for each sawn semiconductor wafer to have side faces which are as planar as possible and lie parallel to one another.

Deviations from the ideal wafer shape are described, inter alia, by the parameters warp and bow.

The so-called warp of the wafers is a known measure of the deviation of the actual wafer shape from the desired ideal shape. The warp should generally amount to at most a few micrometers (μm).

The bow is a measure of the convex or concave deformation of a wafer and should in general be at most a few micrometers (μm).

The warp and bow of the wafers are essentially caused by a relative movement of the sawing wire sections relative to the workpiece, which takes place in the axial direction with respect to the workpiece in the course of the sawing process. This relative movement may for example be the result of cutting forces which occur during the sawing, axial displacements of

the wire guide rollers due to thermal expansion, bearing plays or thermal expansion of the workpiece.

US application US 2010/0089377A1 teaches a method for cutting a multiplicity of wafers from a workpiece, in which the warp and the bow of the wafers are reduced. To this end, the displacements of the workpiece and of the wire web in the axial direction are respectively measured and correspondingly adapted.

During the cutting of wafers from a workpiece, strong mechanical and thermal loading of the sawing wire in the wire web occurs, which can lead to unplanned interruption of the wire sawing process due to wire breaking (wire fracture).

In order to avoid wire breakages when cutting a workpiece into a multiplicity of wafers by means of a wire web, laid-open specification DE 10 2011 008 397 A1 teaches the application of a torque detection device on the stationary axle of a deflection pulley, so that an excessively large tensile stress applied to the sawing wire can be avoided.

In the event of a wire breakage, the sawing process must be interrupted as rapidly as possible in order to avoid damage to the wire saw and the material to be cut.

In order to be able to identify a wire breakage immediately and to be able to stop the wire saw process within the shortest possible time, WO 2011/151022 A1 discloses a method for monitoring wire breakages when cutting a workpiece by means of wire webs, in which a direct current is passed through the wire web and generates a voltage, which is monitored by a sensor, over the wire array. In the event of a voltage deviation caused by a wire breakage, the cutting process is interrupted automatically.

After a wire breakage and switching off of the wire saw, the workpiece and the wire web are separated from one another. To this end, for example, the workpiece may be removed upward from the web. After repair, the workpiece is reintroduced into the wire web, optionally with minor movement of the sawing wires in the presence of the cutting medium.

The interruption of the wire sawing process should be as brief as possible, since the sawing wires and guide rolls heated by the cutting into the workpiece cool during shutdown and contraction of the sawing wires and guide rolls may occur. This may lead to impaired nanotopography of the wafer surfaces on resumption of the sawing process.

In order to avoid contraction of the heated sawing wires and guide rolls on unplanned shutdown, publication DE 11 2009 001 747 T5 discloses a method for resuming operation of a wire saw, in which, during the unplanned shutdown, thermal regulation of the workpiece and of the relevant parts of the wire saw (sawing wire and guide rolls) is ensured by the liquid cutting medium. In addition, a displacement magnitude for the guide rolls of the wire web, which corresponds to the displacement of the workpiece on interruption of the process, is set in the axial direction.

For resuming the sawing process, however, the teaching of publication DE 11 2009 001 747 T5 does not take into account the fact that the sawing wire has at least partially a different degree of wear after repair than before the interruption.

For this reason, a deep incision (groove, indentation) may occur in the surface of the wafers to be cut when resuming the wire sawing process, so that in the least favorable case the

wafers are no longer suitable for further processing owing to the inferior surface topography. It is this problem which gives rise to the object of the present invention.

It was an object of the invention to provide a method which, in the event of an unplanned process interruption during the wire sawing of a workpiece of semiconductor material, avoids negative effects on the surface topography of the sawn wafers of semiconductor material when resuming the process.

The object is achieved by a method for resuming an interrupted process for sawing a workpiece 5 into a multiplicity of wafers with a wire saw, comprising a sawing wire 3 which spans a wire web 4 consisting of many wire sections arranged parallel, the sawing wire 3 is unwound from a feed spool 1a with a forward movement and guided over at least one rotatable deflection pulley 2 into the wire web 4, leaves the wire web 4 again via at least one further rotatable deflection pulley 2, is wound onto a take-up spool 1b and, before the interruption, the sawing wire 3 is moved alternately in defined time intervals forward by a length L_1 and backward by a length L_2 ; in order to resume the interrupted process, the wire web 4 penetrates by forward movement with a first speed v_1 of the sawing wire 3 into the existing sawing kerfs of the workpiece 5 with the addition of a liquid sawing medium of the sawing wire 3 until the wire web 4, or the workpiece 5, has reached the position of the interruption of the wire sawing process, and the sawing wire 3 comes to a stop, wherein, when resuming the sawing process, the wire 3 is moved alternately in defined time intervals forward by a length L_3 with a speed v and backward by a length L_4 with a speed v' , L_4 being less than L_3 and a forward movement and a backward movement corresponding to a cycle Z , and during each forward movement, every other forward movement or after an arbitrary number of forward movements the wire length L_3 unwound during the forward movement is

increased, until the wire length L3 corresponds to the wire length L1 of the forward movement before the interruption.

A workpiece is a geometrical body having a surface consisting of at least two parallel plane faces (end faces) and a lateral face, which is formed by parallel straight lines. In the case of a circular-cylindrical body, the end faces are circular areas and the lateral face is convex. In the case of a cuboid cylindrical workpiece, the lateral face is planar.

Although the present invention relates primarily to workpieces of semiconductor material, it is nevertheless usable for sawing a workpiece of any desired material with a wire saw.

A workpiece of semiconductor material is a single crystal or a crystal of semiconductor material, the semiconductor material usually being silicon.

The semiconductor material wafers sawn from the workpiece of semiconductor material have a front side and a rear side, as well as a circumferential edge, and are refined in further processing steps.

Figure 1 shows, in a highly simplified way, the structure of a wire saw for sawing a circular-cylindrical workpiece 5 according to the prior art. The sawing wire 3 is guided from a feed spool 1a via at least one deflection pulley 2 into a wire web 4. The wire web 4 consists of a multiplicity of wire sections, which are arranged parallel and penetrate into the workpiece 5 during the sawing process (Fig. 1a). The wire fed out of the wire web 4 is wound via at least one further deflection pulley 2 onto a take-up spool 1b (Fig. 1b) (wire forward, WF). When the sawing wire 3 is wound back (wire backward, WB), the take-up spool 1b becomes the feed spool 1a

and the feed spool 1a becomes the take-up spool 1b in the wire forward step.

Figure 2a shows the wire speeds v (m/s) for the oscillation (forward and backward movement) of the sawing wire 3 as a function of time t during the wire sawing process according to the reciprocating movement method. A cycle Z of the wire oscillation in this case comprises the period of acceleration of the sawing wire at the start of the forward movement (wire forward) at time t_{01} until the end of the backward movement directly following on from the forward movement of the wire, at time t_{03} . Accordingly, a cycle Z is composed of a forward movement phase (wire forward, WF) and a backward movement phase (wire backward, WB).

Figure 2b shows the wire oscillation in the reciprocating movement method according to the invention for resuming a wire sawing process after an unplanned shutdown. The wire length $L3$ unwound from the feed spool 1a in the forward direction (WF) becomes longer in each cycle until $L3$ is equal to $L1$. In the embodiment shown here by way of example, the wire length $L4$ wound back from the take-up spool 1b in the backward direction (WB) becomes longer in each cycle until $L4$ is equal to $L2$, $L4$ being shorter than $L3$ (not shown).

Figure 3 schematically shows the profile of the surface of a semiconductor material wafer sawn from a workpiece 5. The deep groove in Fig. 3a is a result of the resumption of a wire sawing process after an unplanned shutdown according to the prior art. Fig. 3b shows the profile which results from the resumption of a wire sawing process after an unplanned shutdown with the method according to the invention.

In the method according to the invention, a conventional wire saw is used. The workpiece 5 to be sawn is generally fixed on a

sawing strip, which is clamped with a mounting plate in the wire saw. The sawing of the workpiece is carried out with a wire web 3.

The wire web 3 of the wire saw is formed by a multiplicity of parallel wire sections which are tensioned between at least two (and optionally three, four or more) wire guide rollers 6, the wire guide rollers 6 being mounted rotatably and at least one of the wire guide rollers 6 being driven. The wire sections generally belong to a single finite wire 3, which is guided spirally around the system of rollers and is unwound from a feed spool (wire-stock spool) 1a onto a take-up spool (receiver spool) 1b (Fig. 1a).

The sawing, or penetration, of the wire web 4 into the workpiece 5 is carried out with a forward feed device, which moves the workpiece 5 against the wire web 4, the wire web 4 against the workpiece 5 or the workpiece 5 and the wire web 4 against one another (cutting movement). At the same time, the sawing wire 3 is wound from a feed spool 1a via the wire web 4 onto a take-up spool 1b (Fig. 1b).

A liquid cutting medium is preferably applied to the wire sections of the wire web 4 by means of nozzles (not shown).

Both wire saws in which the sawing wire in the wire web contains fixedly bonded abrasives, for example diamond abrasive or silicon carbide, and wire saws in which the sawing wire does not have an abrasive coating and the cutting power is provided by a cutting suspension containing abrasives, which is applied onto the sawing wire during or before the sawing process, are suitable for the method according to the invention.

All liquid media according to the prior art are suitable as cutting media. Preferably, glycol, oil or water is used as a carrier material and silicon carbide as abrasive.

The workpiece 5 to be sawn is fastened by means of a sawing strip on a holding device (not shown) in such a way that the end faces 5a are aligned parallel with the wire sections of the wire web 4. During the sawing process, the forward feed device induces a mutually directed relative movement of the wire sections and the workpiece 5. As a consequence of this forward feed movement, the wire 3, to which a cutting medium is applied, works by material erosion through the workpiece 5 to form parallel sawing kerfs, with a comb resulting from the wafers being formed.

The wire sawing of semiconductor material workpieces is preferably carried out according to the so-called reciprocating movement method (wire oscillation method, pilgrim step motion method), that is to say the sawing wire is moved alternately forward and backward in the wire web by a suitable drive, with a forward movement phase WF1, comprising an acceleration phase, a defined time period with a constant speed v of the sawing wire 3 and a deceleration phase until the sawing wire comes to a stop, and a backward movement phase WB2, comprising an acceleration phase in the opposite direction, a defined time period with a constant speed v' of the sawing wire 3 in the opposite direction and a deceleration phase until the sawing wire comes to a stop, corresponding to a cycle Z (Fig. 2a).

From time t_{01} to time t_1 , the sawing wire 3 is accelerated in the forward direction (WF) until the speed v is reached. The sawing wire 3 is moved forward in the time interval t_1 to t_2 with a defined and constant speed v . In the time period t_2 to t_{02} , the forward speed is reduced to 0 m/s (Fig. 2a).

From time t_{02} , the speed of the sawing wire 3 in the backward direction (WB) is accelerated to a speed v' until time t_3 , the backward movement of the sawing wire 3 taking place with the constant speed v' until time t_4 . In the time period t_4 to t_{03} , the backward speed is reduced to 0 m/s (Fig. 2a).

The speed v or v' , respectively, of the sawing wire is preferably 5 - 20 meters per second (hereafter m/s), particularly preferably 10 - 15 m/s.

While the wire 3 is being moved in the forward direction in the time interval t_{01} to t_{02} (= WF1), a wire length $L1$ is unwound from the feed spool 1a and a corresponding wire length $L1$ is wound onto the take-up spool 1b.

In the time period t_{02} to t_{03} (= WB2), in which the wire 3 is moved in the backward direction, a wire length $L2$ is unwound again from the take-up spool 1b and a corresponding wire length $L2$ is wound back onto the feed spool 1a, with $L2 < L1$.

The length $L1$ is preferably from 200 m to 500 m, particularly preferably from 300 m to 400 m.

The length $L2$ preferably corresponds to from 30% to 90% of the length $L1$.

Since $L2$ is shorter than $L1$, with each sawing cycle Z a defined length $L(\text{new})$ ($L(\text{new}) = L1 \text{ minus } L2$) of fresh wire is fed into the wire web 4 in order to minimize the wire wear.

The time period for a cycle Z (= WF1 + WB2) is constant throughout the wire sawing process.

If a wire breakage or another unplanned event, for example an electrical or mechanical fault, now leads to an interruption of

the wire sawing process, the wire sawing process consisting of the wire drive and the cutting movement is automatically terminated and the wire saw is brought to a stop in a controlled way within a few seconds after the wire breakage or the other unplanned event.

The signal for terminating the sawing process is triggered automatically by at least one monitoring device internal to the system. A monitoring device may, for example, consist of electrical wire breakage monitoring or a ground short circuit signal.

The ground short circuit signal is triggered by contact of the broken sawing wire with a metal surface.

In the case of a wire breakage, the broken wire is removed manually from the workpiece if necessary.

After an unplanned interruption of the wire sawing process, the workpiece 5 is removed from the wire web 4.

The resumption of the wire sawing process takes place after repair or optionally replacement of the sawing wire 3 or the resolution of another fault.

The resumption of an interrupted wire sawing process begins with introduction of the wire web 4 into the already existing sawing kerfs in the workpiece 5. The sawing wire is in this case preferably wound with a low speed v_1 , preferably 0.1 - 0.5 m/s, in the "wire forward" direction from the feed spool through the wire web onto a take-up spool, and the wire web 4, formed by the wire sections arranged parallel, is reintroduced into the workpiece 5 in the presence of the cutting medium until the position at the time of the interruption is reached.

When the wire web 4, or the workpiece 5 to be sawn, has again reached the position at the time of the interruption, i.e. the wire sections of the wire web 4 have reached the upper end of the respective sawing kerfs, the wire introduction process is ended and the forward winding of the sawing wire is stopped (wire speed 0 m/s).

In another embodiment, when the wire web 4, or the workpiece 5 to be sawn, has again reached the position at the time of the interruption, the resumption of the wire sawing process is started without stopping the forward winding of the sawing wire.

The resumption of the wire sawing process after an unplanned interruption is preferably carried out in the "wire forward" direction, since in this way little used sawing wire 3 enters the already existing sawing kerfs in the workpiece 5 via the wire web 4 from the stock spool.

If the wire sawing process is started after the unplanned interruption immediately with the same wire oscillation, that is to say the same ratio of the wire lengths L_1 (wire forward) to L_2 (wire backward) as before the unplanned interruption, the formation of saw incisions (grooves) on the surfaces of the wafers sawn from the workpiece 5 occurs owing to the different degree of wear of the sawing wire 3 before and after the unplanned interruption. The depth of the saw incisions in the wafer surface may then locally be several times deeper (Fig. 3a), so that the minimum sawing thickness of the sawn wafer may not be attained.

With the method according to the invention for resuming an interrupted wire sawing process, the depth of the saw incisions due to the different degree of wear of the sawing wire 3 before and after the unplanned interruption on the surfaces of the

wafers sawn from the workpiece is minimized (Fig. 3b), which has a positive effect on the minimum sawing thickness of the wafers sawn from the workpiece.

The method according to the invention is characterized by a special wire oscillation, that is to say a movement of the sawing wire through the workpiece by a length $L3$ which is initially not equal to the length $L1$ in one direction (wire forward, WF3) and a length $L4$ which is equal to or initially not equal to the length $L2$ in the other direction (wire backward, WB4).

In the wire forward phase WF3 of the cycle Z in the method according to the invention, the wire length $L3$ at the start of the resumption of the wire sawing process, that is to say in the first cycle or cycles, is less than 95% of the wire length $L1$ of the forward movement phase WF1 of the regular wire sawing process.

Preferably, $L3$ at the start of the resumption of the wire sawing process is reduced by between 5% and 90% relative to $L1$, and particularly preferably $L3$ is reduced by between 10% and 70% relative to $L1$.

In this way, the length of fresh wire during the resumption of the wire sawing process is reduced in comparison with the wire sawing process before the interruption, and the risk of deep sawing incisions being formed during the resumption is significantly reduced (Fig. 3).

In a first embodiment of the method according to the invention, the length $L3$ is increased (lengthened) linearly by a constant value with each cycle Z , until the length $L1$ of the forward movement phase WF1 before the interruption is reached again. Preferably, the length $L3$ is lengthened by 1 to 40%,

particularly preferably by 2 to 20%, of the length L1 with each cycle, until the length L3 is equal to the length L1.

In a second embodiment of the method according to the invention, the length L3 is increased (lengthened) nonlinearly with each cycle, until the length L1 before the interruption is reached again. Preferably, the length L3 is lengthened by 1 to 40%, particularly by 2 to 20%, relative to the length L3 in the first cycle after the resumption, until the length L3 is equal to the length L1.

In a third embodiment of the method according to the invention, the length L3 is increased linearly or nonlinearly with every other cycle, or another arbitrary cycle number, until the length L1 before the interruption is reached again. Preferably, the length L3 is lengthened by 1 to 40%, particularly by 2 to 20%, relative to the length L3 in the first cycle after the resumption, until the length L3 is equal to the length L1.

The number of cycles of the method according to the invention for resuming an interrupted wire sawing process, until the cycle in which $L3 = L1$ (normal operation), depends on the respective embodiment and on the respective lengthening of the length L3.

Preferably, the number of cycles before the normal operation is reached is at least 12, particularly preferably at least 8 cycles.

Independently of the aforementioned embodiments, the wire length L4 wound back in the method according to the invention during the backward movement phase WB4 of the cycle Z may be equal to or initially different from the length L2.

The length L_4 is shorter than L_3 , so that, depending on the embodiment, a defined length $L(\text{new})$ ($L(\text{new}) = L_3 \text{ minus } L_4$) of fresh wire is introduced into the wire web 4 with each sawing cycle, every other sawing cycle or another arbitrary cycle number Z , in order to minimize the wire wear.

If the wire length L_4 in the wire backward phase WB4 is initially different from the length L_2 , the length L_4 preferably corresponds to a fixed fraction of L_3 . In this case, the length L_4 becomes somewhat greater with every sawing cycle, every other sawing cycle or an arbitrary number of sawing cycles, until the length L_4 corresponds to the length L_2 before the interruption of the wire sawing process.

If, for example, the length of L_3 is 150 m in the first cycle WF3-1 and $L_3 = 200$ m in the second cycle WF3-2, then the backward winding length L_4 of the sawing wire may be 75 m in the first cycle WB4-1 and 100 m in the second cycle WB4-2.

Particularly preferably, the length L_4 is equal to the length L_2 , that is to say the length of the wire wound back is the same both when resuming the interrupted sawing process and in the regular sawing process. In this embodiment, the wire length L_4 wound back remains constant, while the wire length L_3 wound forward becomes greater, or is lengthened, in the next or next but one sawing cycle or after an arbitrary number of sawing cycles, until $L_3 = L_1$.

The speed v or v' , respectively, of the sawing wire, that is to say the speed with which the sawing wire is wound forward or back in the time interval t_1 to t_2 or t_3 to t_4 during the method according to the invention, is preferably 5 to 20 m/s, particularly preferably 10 to 15 m/s.

Preferably, the speed v with which the sawing wire is moved forward in the time interval t_1 to t_2 is equal to the speed v' with which the sawing wire is moved backward in the time interval t_3 to t_4 (Fig. 2a).

Likewise preferably, the speed v with which the sawing wire is moved forward in the time interval t_1 to t_2 is not equal to the speed v' with which the sawing wire is moved backward in the time interval t_3 to t_4 .

When the resumption of the interrupted sawing process is completed, that is to say $L_3 = L_1$ and optionally $L_4 = L_2$, the sawing of the workpiece is continued directly with the wire sawing cycles and the speed of the sawing wire which were set before the interruption.

Patent Claims:

1. A method for resuming an interrupted process for sawing a workpiece 5 into a multiplicity of wafers with a wire saw, comprising a sawing wire 3 which spans a wire web 4 consisting of many wire sections arranged parallel, the sawing wire 3 being unwound from a feed spool 1a with a forward movement and guided over at least one rotatable deflection pulley 2 into the wire web 4, leaving the wire web 4 again via at least one further rotatable deflection pulley 2, being wound onto a take-up spool 1b and, before the interruption, the sawing wire 3 being moved alternately in defined time intervals forward by a length L_1 and backward by a length L_2 ;
in order to resume the interrupted process, the wire web 4 penetrating by forward movement with a first speed v_1 of the sawing wire 3 into the existing sawing kerfs of the workpiece 5 with the addition of a liquid sawing medium of the sawing wire 3 until the wire web 4, or the workpiece 5, has reached the position of the interruption of the wire sawing process, and the sawing wire 3 comes to a stop, wherein, when resuming the sawing process, the wire 3 is moved alternately in defined time intervals forward by a length L_3 with a speed v and backward by a length L_4 with a speed v' , L_4 being less than L_3 and a forward movement and a backward movement corresponding to a cycle Z , and during each forward movement, every other forward movement or after an arbitrary number of forward movements the wire length L_3 unwound during the forward movement is increased, until the wire length L_3 corresponds to the wire length L_1 of the forward movement before the interruption.
2. The method as claimed in claim 1, wherein the length L_3 is increased linearly or nonlinearly with each cycle Z , every other cycle Z or after an arbitrary number of cycles Z ,

until the length L_3 is equal to the length L_1 before the interruption.

3. The method as claimed in one of claims 1 and 2, wherein the length L_4 is equal to the length 2.
4. The method as claimed in one of claims 1 and 2, wherein the length L_4 is shorter than L_2 and the length L_4 is increased linearly or nonlinearly with each cycle Z , every other cycle Z or after an arbitrary number of cycles Z , until the length L_4 is equal to the length L_2 .
5. The method as claimed in one of claims 1 and 2, wherein the length L_3 increases by 1 to 40% with each cycle Z , every other cycle Z or after an arbitrary number of cycles Z , until the length L_3 is equal to the length L_1 before the interruption.
6. The method as claimed in one of claims 1 to 5, wherein the length L_3 in the first cycle corresponds to between 5 and 90% of the length L_1 .
7. The method as claimed in one of claims 1 to 6, wherein the speed v with which the wire is moved forward is equal to the speed v' with which the wire is moved backward.
8. The method as claimed in one of claims 1 to 6, wherein the speed v with which the wire is moved forward is not equal to the speed v' with which the wire is moved backward.